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(21) International Application Number: PCT/US00/04082 (22) International Filing Date: 17 February 2000 (17.02.00) (30) Priority Data: 9903925.7 19 February 1999 (19.02.99) EP (71) Applicant (for all designated States except US): THE PROCTER & GAMBLE COMPANY [US/US]; One Procter & Gamble Plaza, Cincinnati, OH 45202 (US). (72) Inventors; and (75) Inventors/Applicants (for US only): BELL, Michael, David [GB/GB]; 61 Masefield Gardens, Crowthorne, Berkshire RG45 7QS (GB). ROLLS, Richard, George, Albert [CA/GB]; 4 Bison Court, 30 Hounslow Road, Feltham TW14 9DD (GB). ELLIOTT, Russell, Philip [GB/GB]; 14 Nobles Way, Egham, Surrey TW20 9RJ (GB). DUKE, Roland, Philip [GB/GB]; 15 Camellia Way, Wokingham, Berks RG41 3NB (GB). (74) Agents: REED, T., David. et al.; The Procter & Gamble Company, 5299 Spring Grove Avenue, Cincinnati, OH 45217-1087 (US).		(81) Designated States: AE, AL, AM, AT, AT (Utility model), AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, CZ (Utility model), DE, DE (Utility model), DK, DK (Utility model), DM, EE, EE (Utility model), ES, FI, FI (Utility model), GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SK (Utility model), SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published <i>Without international search report and to be republished upon receipt of that report.</i>
(54) Title: COSMETIC COMPOSITIONS (57) Abstract A leave-on cosmetic composition suitable for topical application to the skin comprising: a) a polymeric thickening agent selected from non-ionic and anionic thickening agents, or mixtures thereof, having a number average molecular weight of greater than 20,000 and; b) a cation containing polymer, or mixtures thereof wherein said composition comprises less than 4 % of an anionic, zwitterionic, or amphoteric surfactant. The compositions of the invention display low levels of tack, as well as good rheological, absorption and insulation properties, in addition to skin feel, skin softness and skin smoothness benefits.		

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